

SUBSTRATE TREATMENT APPARATUS AND REACTION TUBE

ABSTRACT

The present disclosure is to suppress an adhesion of by-products to the vicinity of a furnace opening member. A substrate treatment apparatus includes a reaction tube provided therein with a substrate treatment region in which a substrate is treated; and a furnace opening member disposed in a lower portion of the reaction tube. The reaction tube includes a protrusion portion formed to protrude outward in the lower portion of the reaction tube, and an extension portion formed to extend downward from a lower end of the reaction tube. The extension portion is formed to have a thickness larger than a thickness of the reaction tube at a position corresponding to the substrate treatment region. The extension portion is configured to cover an inner circumferential surface of the furnace opening member.

FIGURE 2